



## Brion

The move to the 10-nm node and beyond presents significant challenges to the semiconductor industry. Complex patterning technologies require an integrated approach to IC design, mask creation, lithography, etch and deposition, and metrology. The ability to co-optimize all these aspects of the patterning process is a corner stone of ASML's Holistic Lithography vision.

ASML Brion is a world leader in computational lithography with a comprehensive suite of solutions in the process-window enhancement and in the process-window control space, addressing the key patterning challenges that face the industry today, whether related to overlay or to imaging, and covering both state-of-the-art multi-patterning and EUV applications.

